Docket No.

210148US99

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Jamal RAMDANI, et al.

SERIAL NO:

09/885,409

FILED:

June 21, 2001

FOR:

EXAMINER: SIMKOVIC METHOD FOR FABRICATING A SEMICONDUCTOR STRUCTURE INCLUDING A METAL OXIDE

INTERFACE WITH SILICON

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

ASSISTANT COMMISSIONER FOR PATENTS WASHINGTON, D.C. 20231

SIR:

Applicant(s) wish to disclose the following information.

#### REFERENCES

The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references were submitted in application Serial No. 09/908,888 according to the attached copy of a Granted Petition. This application contains related subject matter.

A check is attached in the amount required under 37 CFR §1.17(p).

### **RELATED CASES**

Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.

A check is attached in the amount required under 37 CFR §1.17(p).

#### **CERTIFICATION**

☐ Each item of information contained in this information disclosure statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.

□ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

## **DEPOSIT ACCOUNT**

Please charge any additional fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

03/19/2003 CV0111 00000160 09885409

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Respectfully submitted,

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GAU:

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	XAMINER	Т	DOCUMENT	DATE	NAME	CLASS	SUB	FILING DATE	
	INITIAL A		NUMBER	04/09/74	Ladany et al.		CLASS	IF APPROPRIATE	
					Matthews et al.	ļ			
	AE		1,174,422		· · · · · · · · · · · · · · · · · · ·				
	AC				Manasevit	<u> </u>			
L	AE		1,482,906		Hovel et al.				
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L	AF				Manasevit				
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	AH		<u></u>		Kay et al.	<u></u>			
	AJ	<u>.</u>	1,855,249		Akasaki et al.				
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	Ar		<u></u>		Aslam et al.				
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	AC		5,159,413		Calviello et al.				
	AF		5,173,474		Connell et al.				
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	AΤ		5,393,352		Summerfelt				
	Αl		5,418,216		Fork	ļ			
	A\		5,450,812		McKee et al.				
	AV		5,478,653		Guenzer				
	A		5,482,003		McKee et al.	ļ			
	A\		5,514,484		Nashimoto			r <u>-                                    </u>	
	AZ		5,556,463		Guenzer				
	BA		5,588,995		Sheldon				
	ВЕ	3 5	5,670,798	09/23/97	Schetzina				
	ВС		· · ·		Fork et al.		_		
	ВС		5,735,949		Manti et al.				
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	BF		5,810,923	09/22/98	Yano et al.				
	ВС		5,830,270		McKee et al.				
	Bl		5,912,068	06/15/99	Jia				
	ВІ		6,020,222		Wollesen				
	BJ		5,045,626	04/04/00	Yano et al.				
	Вн		5,064,078	<u> </u>	Northrup et al.				
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	BN		5,096,584		Ellis-Monaghan et al.				
	BN		3,103,008		McKee et al.				
	ВС		5,136,666		So				
	BF		5,174,755		Manning	<b> </b>			
	BC	<b>∑</b> €	5,180,486	01/30/01	Leobandung et al.				

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INITIAL	CALED	3,766,370	10/16/73	Walther		02.00	11 / 11 / 11 / 11 / 11
		4,006,989	02/08/77	Andringa			
		4,284,329	08/18/81	Smith et al.			
		4,777,613	10/11/98	Shahan et al.		<del>  </del>	
		4,802,182	01/31/89	Thornton et al.		<del>                                     </del>	
		4,882,300	11/21/89	Inoue et al.			
	CG	4,896,194	01/23/90	Suzuki			
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	CI	5,081,062	10/13/92	Inam et al.			
	CI	5,155,658	09/28/93	Ramesh			
	СК	5,248,564	11/09/93	Tazaki et al.		<del> </del>	
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	СМ	5,270,298	02/15/94	Taddiken			
	CN	5,286,985		Oishi et al.			
	СО	5,310,707	05/10/94	Summerfelt		<del> </del>	
	СР	5,326,721	07/05/94				
	ca	5,404,581	04/04/95	Honjo			
	CR	5,418,389	05/23/95	Watanabe			
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	СТ	5,576,879	11/19/96	Nashimoto			
	CU	5,606,184	02/25/97	Abrokwah, et al.			
	CV	5,640,267	06/17/97	May et al.		-	
	cw	5,674,366	10/07/97	Hayashi et al.			
	СХ	5,729,641	03/17/98	Chandonnet et al.			
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	CZ	5,825,799	10/20/98	Ho et al.			
	DA	5,857,049	01/05/99	Beranek et al.			
	DB	5,874,860	02/23/99	Brunel et al.			
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-	DG	6,002,375	12/14/99	Corman et al.			
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VITIAL	<u> </u>	NUMBER				CLASS	IF APPROPRIATE		
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	EX	5,801,105	09/01/98	Yano et al.					
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	FA	5,861,966	01/19/99	Ortel		<u> </u>			
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	FD	6,058,131	05/02/00	Pan			1		
	FE	6,137,603	10/24/00	Henmi					
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	FG	6,173,474	01/16/01	Conrad					
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	FJ	4,398,342	08/16/83	Pitt et al.		†			
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<u> </u>	FM	4,482,422	11/84	McGinn et al.		<del> </del>			
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	FP	4,841,775		Ikeda et al.		<del> </del>	+		
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	IB	5,656,382	08/12/97	Nashimoto					
	IC	5,659,180	08/19/97	Shen et al.	-	1.			
	ID	5,661,112	08/26/97	Hatta et al.			****		
	ΙE	5,679,965	11/95	Schetzina					
	IF	5,725,641	03/10/98	MacLeod					
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	īН	5,776,621	07/07/98	Nashimoto					
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	IJ	5,789,845	08/04/98	Wadaka et al.					
<del> </del>	IK	5,792,569	08/11/98	Sun et al.			· · · · · · · · · · · · · · · · · · ·		
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	IM	5,796,648	08/18/98	Kawakubo et al.					
<u></u>	IN	5,801,072	09/01/98	Barber			··· ··· ··· ·		
	10	5,812,272	09/22/98	King et al.			· · · · · · · · · · · · · · · · · · ·		
	IP	5,814,583	09/98	Itozaki et al.					
	IQ	5,825,055	10/20/98	Summerfelt		†			
	IR	5,827,755	10/27/98	Yonchara et al.			,		
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·-·	iT	5,838,035	11/17/98	Ramesh					
	ΙÜ	5,844,260	12/01/98	Ohori					
<u>.                                    </u>	IV	5,846,846	12/08/98	Suh et al.			<del></del>		
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	IX	5,872,493	02/16/99	Ella		1			
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	JA	5,883,564	03/16/99	Partin		<del>                                     </del>			
	JB	5,907,792	05/25/99	Droopad et al.					
	JC	5,937,274	08/10/99	Kondow et al.			······································		
	ND D	5,948,161	09/07/99	Kizuki		<del>                                     </del>			
	JE	5,959,879	09/28/99	Koo		† †			
	JF	5,966,323	10/99	Chen et al.		+	- ··································		
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Form PTO 1449
(Modified)

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. SERIAL NO. 210148US99 09/885,409

APPLICANT

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	KP	5,528,067	06/18/96	Farb et al.				
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	LE	6,239,449	05/29/01	Fafard et al.				
	LF	2001/0013313	08/16/01	Droopad et al.				
	LG	6,184,044	02/06/01	Sone et al.				
	LH	6,011,646	01/04/00	Mirkarimi et al.	-			
	Li	5,227,196	07/13/93	Itoh				
	LJ	6,150,239	11/21/00	Goesele et al.				
	LK	5,441,577	08/15/95	Sasaki et al.				
	LL	4,459,325	07/10/84	Nozawa et al.				
	LM	4,392,297	07/12/83	Little				
<u> </u>	LN	4,289,920	09/15/81	Hovel			· · · · · · · · · · · · · · · · · · ·	
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	MC	6,229,159	05/08/01	Suzuki			——————————————————————————————————————
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			<del></del>
	MG	6,108,125	08/22/00	Yano			· · · · · · · · · · · · · · · · · · ·
	МН	5,073,981	12/17/91	Giles et al.			
	MI	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	Ho et al.			<del></del>
	MK	6,362,017	03/26/02	Manabe et al.			
	ML	6,242,686	06/05/01	Kishimoto et al.			
	MM	5,689,123	11/18/97	Major et al.			
<b>м</b>	MN	5,670,800	09/23/97	Nakao et al.			<del></del>
	МО	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.		<del> </del>	
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			
,;; <u> </u>	MT	6,093,302	07/25/00	Montgomery			
-	MU	6,372,813	04/16/02	Johnson et al.		<del> </del>	
	MV	5,608,046	03/04/97	Cook et al.			***************************************
	MW	5,955,591	09/21/99	Imbach et al.			
	MX	6,022,963	02/08/00	McGall et al.			
	MY	6,083,697	07/04/00	Beecher et al.			
		5,063,081	11/05/91	Cozzette et al.			*****
	NA	5,479,317	12/26/95	Ramesh			·
	NB	5,306,649	04/26/94	Hebert			
	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			22222
	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina		<del>                                     </del>	
-	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.		<del>                                     </del>	
	NJ	5,280,013	01/18/94	Newman et al.		<del>                                     </del>	
	NK	6,348,373 B1	02/19/02	Ma et al.		<u> </u>	
	NL	6,339,664 B1	01/15/02	Farjady et al.			
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.		1	
	NP	6,011,641	01/04/00	Shin et al.		+	
	1117	0,011,041	01/04/00	Similet at.		<del>                                     </del>	

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ATTY DOCKET NO. 210148US99 **APPLICANT** 

SERIAL NO. 09/885,409

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	OA	5,807,440	09/15/98	Kubota et al.			
	ОВ	4,681,982	07/21/87	Yoshida			
	ОС	4,629,821	12/16/86	Bronstein-Bonte et al.			
	OD	4,452,720	06/05/84	Harada et al.			
	OE	3,935,031	01/27/76	Adler			
	OF	5,760,426	06/02/98	Marx et al.			
	OG	5,053,835	10/01/91	Horikawa et al.			
	ОН	6,326,645 B1	12/04/01	Kadota			•
	OI	5,770,887	06/23/98	Tadatomo et al.			
	OJ	6,372,356 B1	04/16/02	Thornton et al.			
	ОК	4,774,205	09/27/88	Choi et al.			
	OL	6,359,330 B1	03/19/02	Goudard			
	ОМ	5,312,765	05/17/94	Kanber			
	ON	5,734,672	03/31/98	McMinn et al.			
	00	6,367,699 B2	04/09/02	Ackley			
	OP	5,530,235	06/25/96	Stefik et al.			
	OQ	5,623,552	04/22/97	Lane			
	OR	5,481,102	01/02/96	Hazelrigg, Jr.		_	
	os	6,134,114	10/17/00	Ungermann et al.			
	ОТ	5,984,190	11/16/99	Nevill			
	ΟU	5,789,733	08/04/98	Jachimowicz et al.			
	OV	5,753,300	05/19/98	Wessels et al.			
	ow	6,208,453	03/27/01	Wessels et al.			
	OX	5,886,867	03/23/99	Chivukula et al.			
	OY	5,028,976	07/02/91	Ozaki et al.			
	ΟZ	5,869,845	02/09/99	Vander Wagt et al.			
	PA	5,596,214	01/21/97	Endo			
	РВ	6,391,674 B2	05/21/02	Ziegler			
	PC	6,275,122 B1	08/14/01	Speidell et al.			
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	PE	6,210,988 B1	04/03/01	Howe et al.			
	PF	6,392,257	05/21/02	Ramdani et al.			
	PG	4,442,590	04/17/84	Stockton et al.			
	PH	5,603,764	02/18/97	Matsuda et al.			
	Pl	6,087,681	06/11/00	Shakuda			
	PJ	5,132,648	07/21/92	Trinh et al.			
	PK	6,427,066	07/30/02	Grube			
	PL	2002/0072245	06/13/02	Ooms et al.			
	РМ	6,278,138 B1	08/21/01	Suzuki			
	PN	5,888,296	03/30/99	Ooms et al.			
	РО	5,198,269	03/3093	Swartz et al.			
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	QA	5,776,359	07/07/98	Schultz et al.		<u> </u>		
	QB	5,569,953	10/29/96	Kikkawa et al.				
	QC	5,834,362	11/10/98	Miyagaki et al.			<del> </del>	
	QD	6,248,621 B1	06/19/01	Wilk et al.				
	QE	5,266,355	11/30/93	Wernberg et al.				
	QF	6,277,436 B1	08/21/01	Stauf et al.				
	QG	6,039,803	03/21/00	Fitzgerald et al.				
	QH	5,619,051	04/08/97	Endo		ļ	<u> </u>	
•	QI	5,420,102	05/30/95	Harshavardhan et al.				
	۵J	5,210,763	05/11/93	Lewis et al.				
	QK	5,103,494	04/07/92	Mozer				
	QL	4,594,000	06/10/86	Falk et al.				
	QM	4,297,656	10/27/81	Pan				
· · · · · · · · · · · · · · · · · · ·	QN	5,244,818	09/14/93	Jokers et al.			·	
	QO	6,048,751	04/11/00	D'Asaro et al.				
	QP	5,484,664	01/16/96	Kitahara et al.				
	QQ	5,780,311	07/14/98	Beasom et al.				
<u> </u>	QR	6,438,281 B1	08/20/02	Tsukamoto et al.				
	QS	5,399,898	03/21/95	Rostoker				
	QT	6,271,619	08/07/01	Yamada et al.				
	QU	5,334,556	08/02/94	Guldi				
· · · · · · · · · · · · · · · · · · ·	QV	4,910,164	03/20/90	Shichijo				
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	QY	6,306,668 B1	10/23/01	McKee et al.				
	QZ	6,143,366	11/07/00	Lu				
	RA	6,410,941	06/25/02	Taylor et al.				
	RB	5,397,428	03/14/95	Stoner et al.				
	RC	6,432,546 B1	08/13/02	Ramesh et al.				
		6,345,424	02/12/02	Hasegawa et al.				
	RE	6,338,756 B2	01/15/02	Dietze				
	RF	5,516,725	05/14/96	Chang et al.				
	RG	4,667,212	05/19/87	Nakamura				
	RH	5,629,534	05/13/97	Inuzuka et al.			·····	
	RI	3,914,137	10/21/75	Huffman et al.			· · · · · · · · · · · · · · · · · · ·	
	RJ	5,753,928	05/19/98	Krause				
	RK	5,977,567	11/02/99	Verdiell		1		
	RL	5,130,762	07/14/92	Kulick				
	RM	5,621,227	04/15/97	Joshi		1	· · · · · · · · · · · · · · · · · · ·	
	RN	6,389,209 B1	05/14/02	Suhir				
	RO	5,163,118	11/10/92	Lorenzo et al.				
	RP	5,926,493	07/20/99	O'Brien et al.		<del> </del>		
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	RQ	5,323,023	06/21/94	Fork				

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	SA	6,156,581	12/05/00	Vaudo et al.		<u> </u>		
	SB	5,395,663	03/07/95	Tabata et al.		<u> </u>		
<u></u>	sc	4,146,297	03/27/79	Alferness et al.				
	SD	5,452,118	09/19/95	Maruska			· · · · · · · · · · · · · · · · · · ·	
	SE	5,889,296	03/30/99	Imamura et al.		<u> </u>		
	SF	6,300,615 B1	10/09/01	Shinohara et al.		ļ	<u>.</u>	
	SG	6,232,910 B1	05/15/01	Bell et al.				
	SH	5,686,741	11/11/97	Ohori et al.				
	SI	4,959,702	09/25/90	Moyer et al			·	
	SJ	6,100,578	08/08/00	Suzuki				
	SK	6,410,947 B1	06/25/02	Wada				
	SL	6,417,059 B2	07/09/02	Huang				
	SM	6,461,927 B1	10/08/02	Mochizuki et al.				
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	so	5,981,976	11/09/99	Murasato				
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	SR	2002/0131675 A1	09/19/02	Litvin			•	
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	ST	6,278,523 B1	08/21/01	Gorecki				
	SU	6,319,730 B1	11/20/01	Ramdani et al.				
	sv	6,404,027	06/11/02	Hong et al.				
	sw	6,312,819 B1	11/06/01	Jia et al.				
	SX	5,119,448	06/02/92	Schaefer et al.				
	SY	4,120,588	10/17/78	Chaum			***	
	SZ	5,194,917	03/16/93	Regener				
	TA	5,018,816	05/28/91	Murray et al.				
<del></del>	ТВ	5,953,468	09/14/99	Finnila et al.				
	TC	5,561,305	10/01/96	Smith			·	
	TD	5,896,476	04/20/99	Wisseman et al.				
·	TE	4,934,777	06/19/90	Jou et al.				
	TF	6,320,238 B1	11/20/01	Kizilyalli et al.				
<u> </u>	TG	6,393,167 B1	05/21/02	Davis et al.				
·	TH	5,760,427	06/02/98	Onda				
	Ti	6,411,756 B2	06/25/02	Sadot et al.				
	TJ	5,668,048	09/16/97	Kondo et al.		1		
	TK	5,852,687	12/22/98	Wickham				
	TL	5,122,852	06/16/92	Chan et al.				
	ТМ	5,173,835	12/22/92	Cornett et al.				
	TN	5,055,835	10/08/91	Sutton				
	ТО	6,139,483	10/31/00	Seabaugh et al.	<del></del>			
	TP	5,283,462	02/01/94	Stengel		<b>†</b>	<u> </u>	
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	UB	5,427,988	06/27/95	Sengupta et al.					
	UC	6,297,842 B1	10/02/01	Koizumi et al.			<u></u>		
	UD	5,682,046	10/28/97	Takahashi et al.					
	UE	5,181,085	01/19/93	Moon et al.					
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	UG	6,013,553	01/11/00	Wallace et al.					
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	IJ	5,995,528	11/30/99	Fukunaga et al.					
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	US	6,326,637 B1	12/04/01	Parkin et al.					
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ADEMARK	•	DOCUMENT NUMBER	DATE	COUNTRY	TR	ANSLATION
					YES	NO
	AAA	0 250 171	12/23/87	EP	×	<u> </u>
	AAB	0 342 937	11/23/89	EP	×	
	AAC	0 455 526	06/11/91	EP	×	
	AAD	0 602 568	06/22/94	EP	×	
	AAE	0 607 435	07/27/94	EP	×	
	AAF	1 001 468	05/17/00	EP	×	
	AAG	0 514 018	11/19/92	EP	×	
	4AH	0 999 600	05/10/00	EP	×	<del>-  </del>
	AAI	1 319 311	06/04/70	Great Britain	x	
<i></i>	۷ÄJ	5-291299	11/05/93	Japan w/English Abstract	×	
7	AAK	11-238683	08/31/99	Japan	×	
/	AAL	11-260835	09/24/99	Japan w/English Abstract	×	— <del> </del>
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	VAO	52-88354	07/23/77	Japan w/English Abstract	- <del>-</del> X	
	\AP	54-134554	10/19/79	Japan w/English Abstract	<u> </u>	
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	AS	6-232126	08/19/94	Japan	- <del>x</del>	
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A	ĀU	63-34994	02/15/88	Japan w/English Abstract	- <del>x</del>	
	ΑV	63-131104	06/03/88	Japan w/English Abstract	- <del>x</del>	
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	BAC	64-50575	02/27/89	Japan	<del></del>	
	BAD	WO 98/05807	01/12/98	WIPO		
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	BAI	02051220	02/21/90	Japan (English Abstract)		
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E	BAX	0 964 453	12/15/99	Europe		
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